Progress meeting

Victor Calzadilla, Dominik Heiss,
Andrea Fiore, Meint Smit

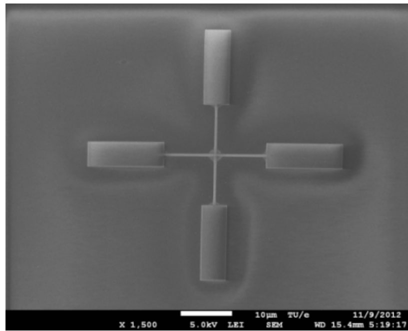
4/02/2013

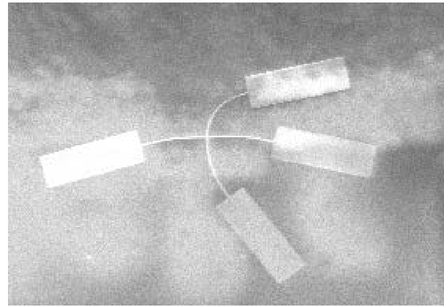
TU/e Technische Universiteit Eindhoven University of Technology

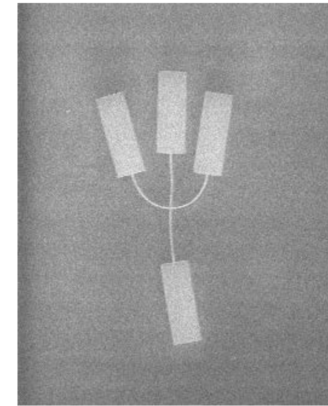
Where innovation starts

Reproducibility

- EBL mark with same dose



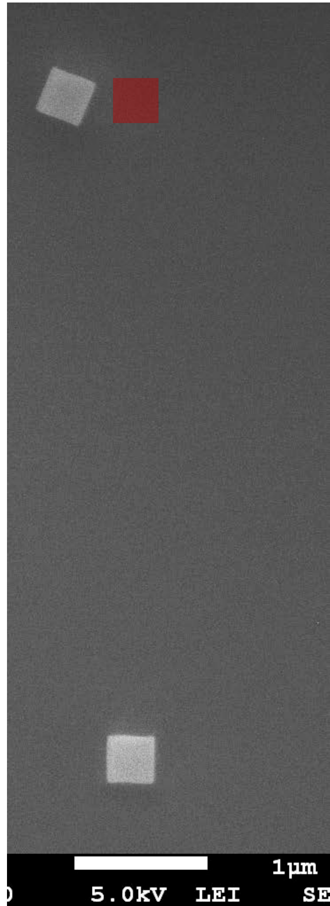




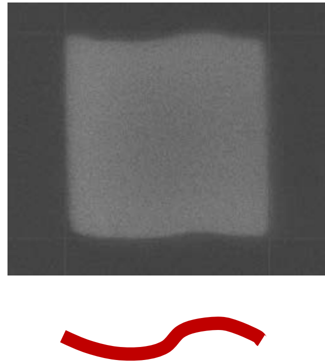
Low reproducibility due to poor adhesion of photoresist (hsq)

Other proofs of adhesion problems

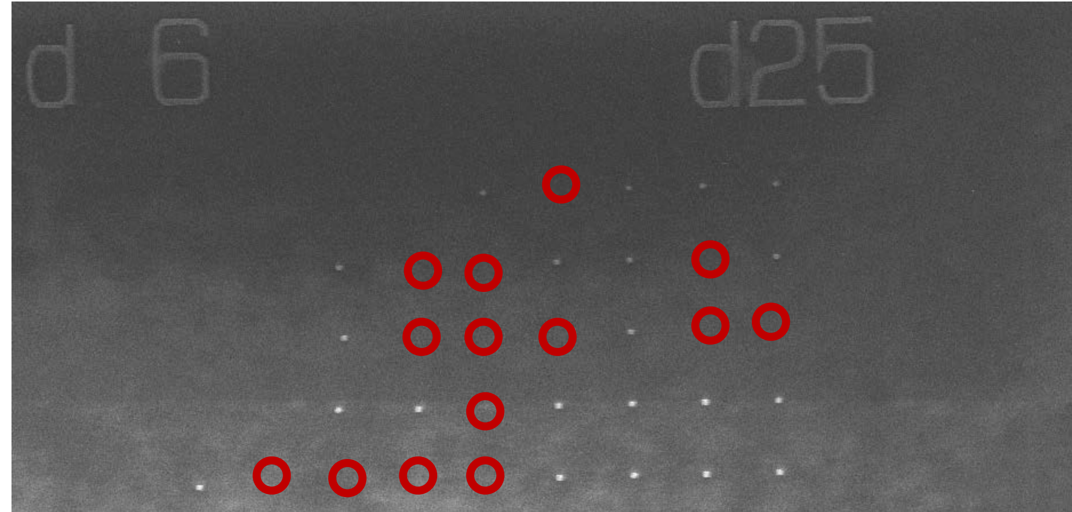
Displacement and rotation



Wavy features



Missing structures in dose test

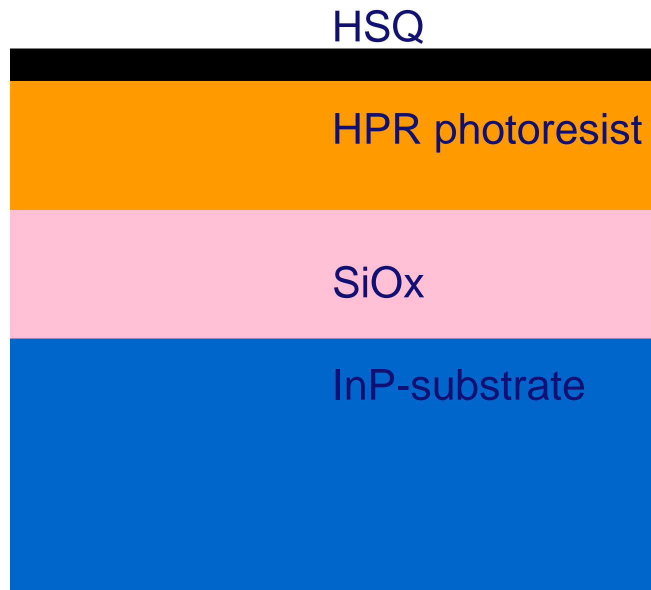


Dose factor
Dose: 100 uC/cm

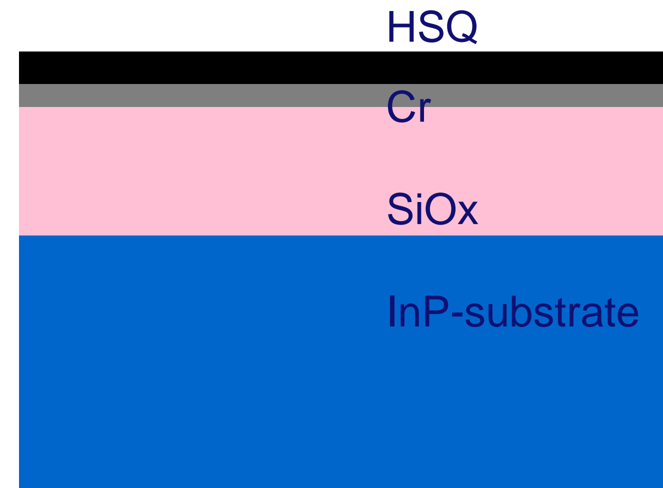
COBRA
TU/e Technische Universiteit Eindhoven University of Technology

Testing of a new masking scheme

- Before



- Under test



- Adhesion ✓
- Transferred roughness ?